

IN THE ABSTRACT:

Please cancel the current abstract and insert the following new abstract therefor.

-- An exposure method of projecting a pattern of an original onto a substrate. The method includes steps of measuring a position of an alignment mark formed on the substrate, projecting the pattern onto the substrate based on a measurement result in the measurement step, and projecting, onto the substrate based on the measurement result, a mark, which has a known relative position from a reference pattern arranged on an original stage and to align the original stage and a substrate stage, and is arranged on the original stage and to form an alignment mark on the substrate. --